DC 마그네트론 스퍼터링 법으로 중착한 ZnO:Al 박막의 기판온도 영향에 따른 특성 연구

Influence of substrate temperature on the properties of Al doped ZnO(ZnO:Al) thin films deposited by direct current magnetron sputtering

<u>Hong Mo Koo</u>, Bo Rae Bang, Yeon Keon Moon, Se Hyun Kim, Chang-Oh Jeong*, Jong Wan Park[†]
Division of Materials Science and Engineering, Hanyang University,

*LCD R&D Center, Samsung Electronics Co, Ltd.
(Iwpakr@hanvang ac kr[†])

A transparent conducing electrode is necessary component in most flat panel display (FPD) In most cased transparent conductive oxide (TCO) consists of a degenerate wide band gap semiconductor with low electrical resistivity and high transparency in the visible and near-infrared wavelength range. The commercially most important material for transparent conducting film nowadays is Sn-doped In2O3 (ITO), owing to its unique characteristics of high visible transmittance (\leq 90%), low dc resistivity, high infra-red reflectance and absorbance in the microwave region. The high quality of ITO films deposited by sputtering of oxide targets has already been successfully achieved on a commercialized production scale.

Transparent conducting aluminum-doped zinc oxide (AZO) thin films have been deposited on corning 1737 glass by DC magnetron sputter. The structural, electrical and optical properties of the films were investigated as a function of various substrate temperatures. AZO thin films were fabricated by dc magnetron sputtering with AZO ceramic target (Al2O3. 2wt %)

The obtained films were polycrystalline with a hexagonal wurtzite structure and preferentially oriented in the (002) crystallographic direction. The lowest resistivity is $6.0\times10^{-4}\Omega$ cm with the carrier concentration of 2.694×1020 cm⁻³ and Hall mobility of 20.426cm²/Vs. The average transmittance in the visible range was above 90%. The more result will be presented in the meeting